Form 1449*	Atty. Docket No.: 303.678US4	Serial No. Unknown
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U.S. PATENT DOCUMENTS

**Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
_____	5,668,035	09/16/1997	Fang, C.H., et al.	438	239	06/10/96
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**Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation Yes | No

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	Chen, Y., et al., "Performance and Reliability Assessment of Dual-Gate CMOS Devices with Gate Oxide Grown Nitrogen Implanted Si Substrates", International Electron Device Meeting, pg. 1-4, (1997)
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*Substitute Disclosure Statement Form (PTO-1449)

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